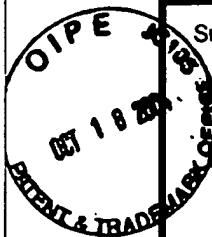


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Application Number	09/905,718
Filing Date	05/16/2001
First Named Inventor	Willson et al.
Group Art Unit	1762
Examiner Name	Pianalto, Bernard D.
Attorney Docket Number	PA27-02Q12

### OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>2</sup>
T.H.M	C1	Papirer et al., "The Grafting of Perfluorinated Silanes onto the Surface of Silica: Characterization by Inverse Gas Chromatography," August 1993, pp238-242, vol. 159, Issue 1.	
	C2	Abstract of Papirer et al., "The Grafting of Perfluorinated Silanes onto the Surface of Silica: Characterization by Inverse Gas Chromatography," August 1993, pp238-242, vol. 159, Issue 1.	
	C3	Hirai et al., "Mold Surface Treatment for Imprint Lithography," August 2001, pp 457-462, vol 14, No. 3.	
	C4	Abstract of Hirai et al., "Mold Surface Treatment for Imprint Lithography," August 2001, pp 457-462, vol 14, No. 3.	
	C5	Sung et al., "Micro/nano-tribological Characteristics of Self-Assembled Monolayer and its Application in Nano-Structure Fabrication," July 2003, pp. 808-818, vol. 255, no. 7.	
	C6	Abstract of Sung et al., "Micro/nano-tribological Characteristics of Self-Assembled Monolayer and its Application in Nano-Structure Fabrication," July 2003, pp. 808-818, vol. 255, no. 7.	
	C7	Roos et al., "Nanoimprint Lithography with a Commercial 4 Inch Bond System for Hot Embossing," October 2001, pp. 427-435, vol. 4343.	
T.H.M	C8	Abstract of Roos et al., "Nanoimprint Lithography with a Commercial 4 Inch Bond System for Hot Embossing," October 2001, pp. 427-435, vol. 4343.	

Examiner Signature	L	Date Considered	12/15/04
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